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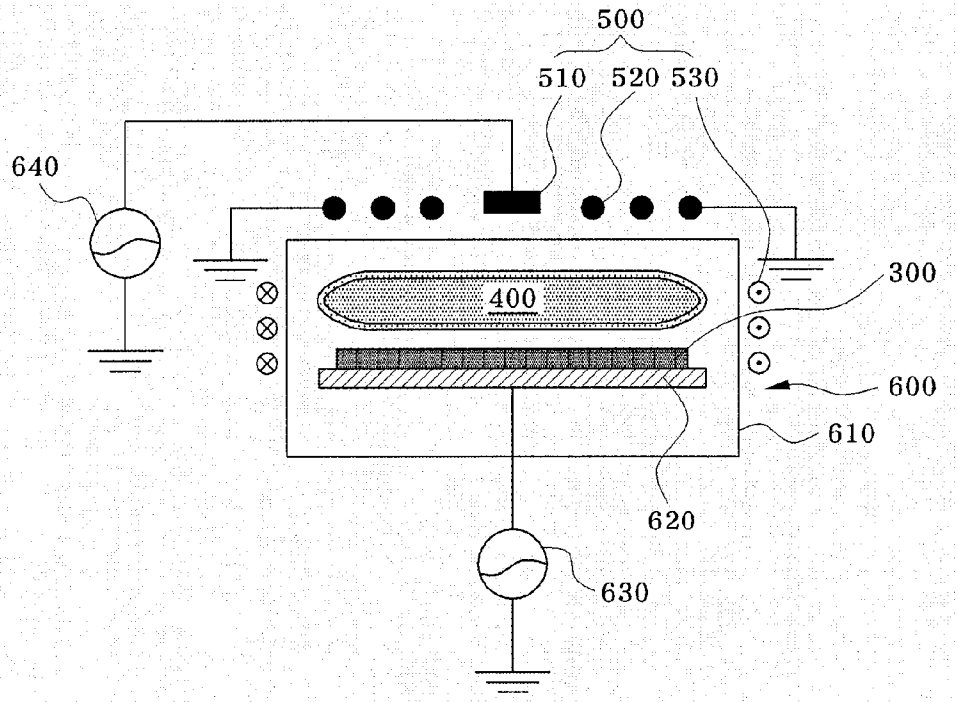
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(54) **Title:** ADAPTIVELY COUPLED PLASMA SOURCE HAVING UNIFORM MAGNETIC FIELD DISTRIBUTION AND PLASMA CHAMBER HAVING THE SAME



(57) **Abstract:** Disclosed is an adaptively coupled plasma source having a uniform magnetic field distribution. The adaptively coupled plasma source includes a flat plate shaped bushing disposed above a reaction chamber in a center region of the reaction chamber, a plurality of upper coils extended from the bushing to be disposed above the reaction chamber, so as to spirally surround the bushing, and a plurality of side coils arranged around a sidewall portion of the reaction chamber to surround the reaction chamber.

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